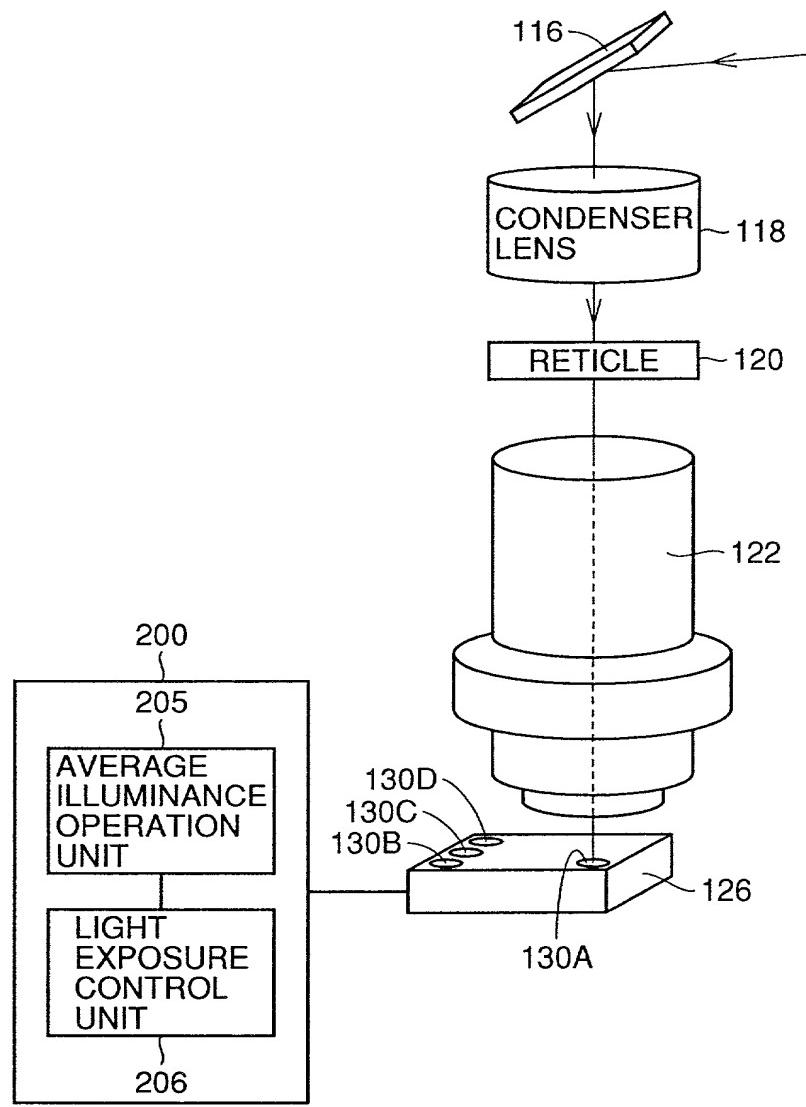


*FIG. 1*



*FIG.2*

200

200A

ILLUMINANCE MEASURING UNIT MEASURING  
ILLUMINANCE BEFORE STARTING EXPOSURE  
OF (N - 1)TH WAFER, DURING (AT LEAST SINGLE)  
EXPOSURE AND AFTER COMPLETION OF EXPOSURE  
WITH ILLUMINANCE METER PROVIDED ON STAGE

200B

RELATIONAL EXPRESSION OPERATION UNIT OBTAINING  
RELATIONAL EXPRESSION (AT LEAST SECONDARY FUNCTION)  
OF ILLUMINANCE AND EXPOSURE TIME FROM ILLUMINANCE  
MEASUREMENT RESULTS OBTAINED FROM ILLUMINANCE  
MEASURING UNIT 200A

200C

FIRST ILLUMINANCE OPERATION UNIT OBTAINING ILLUMINANCE  
AT THE TIME OF STARTING EXPOSURE OF N-TH WAFER AND  
ILLUMINANCE AT THE TIME OF ENDING EXPOSURE WITH  
RELATIONAL EXPRESSION OBTAINED BY RELATIONAL  
EXPRESSION OPERATION UNIT 200B

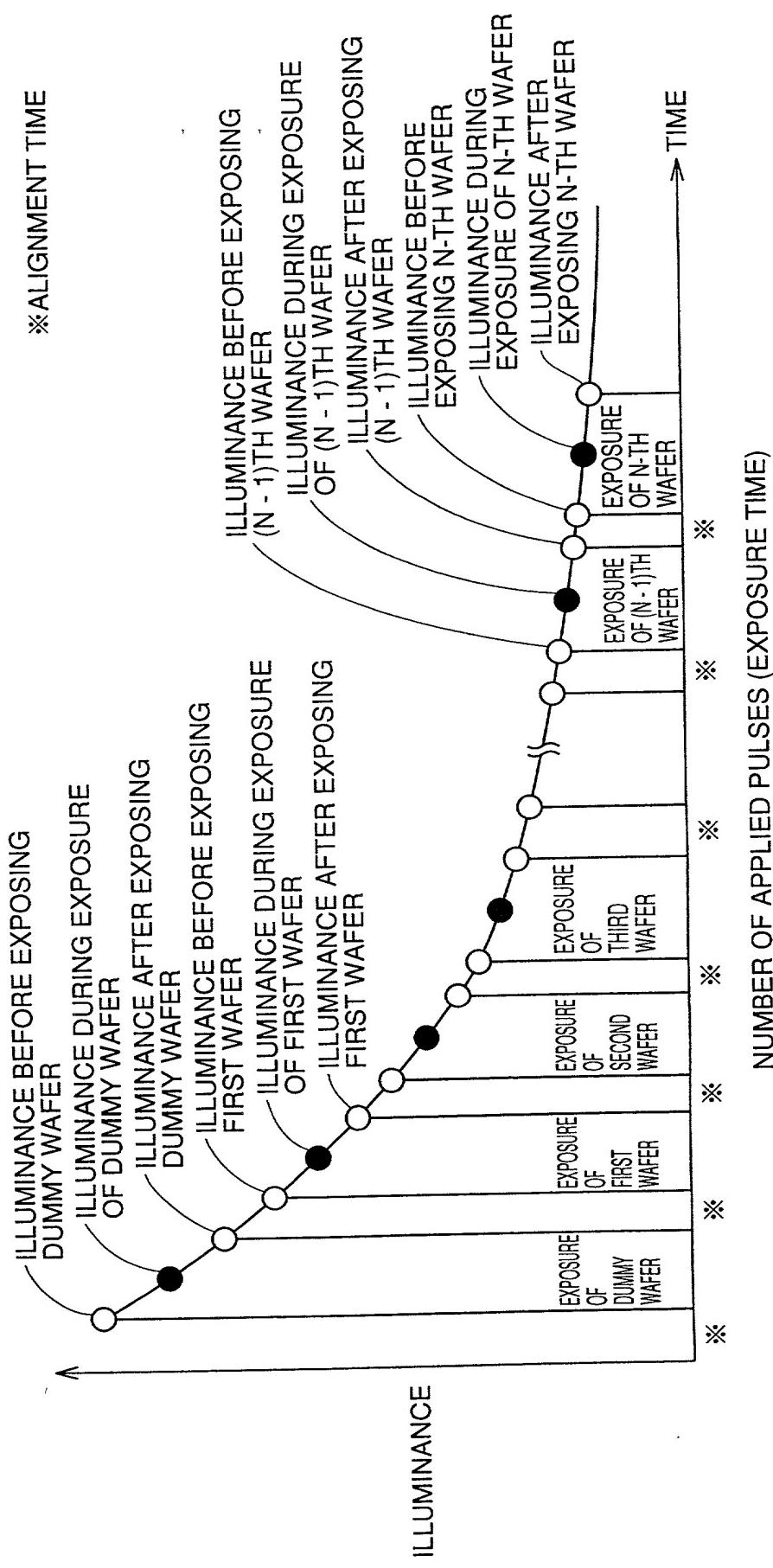
200D

SECOND ILLUMINANCE OPERATION UNIT OBTAINING  
ILLUMINANCE EVERY SHOT OF N-TH WAFER

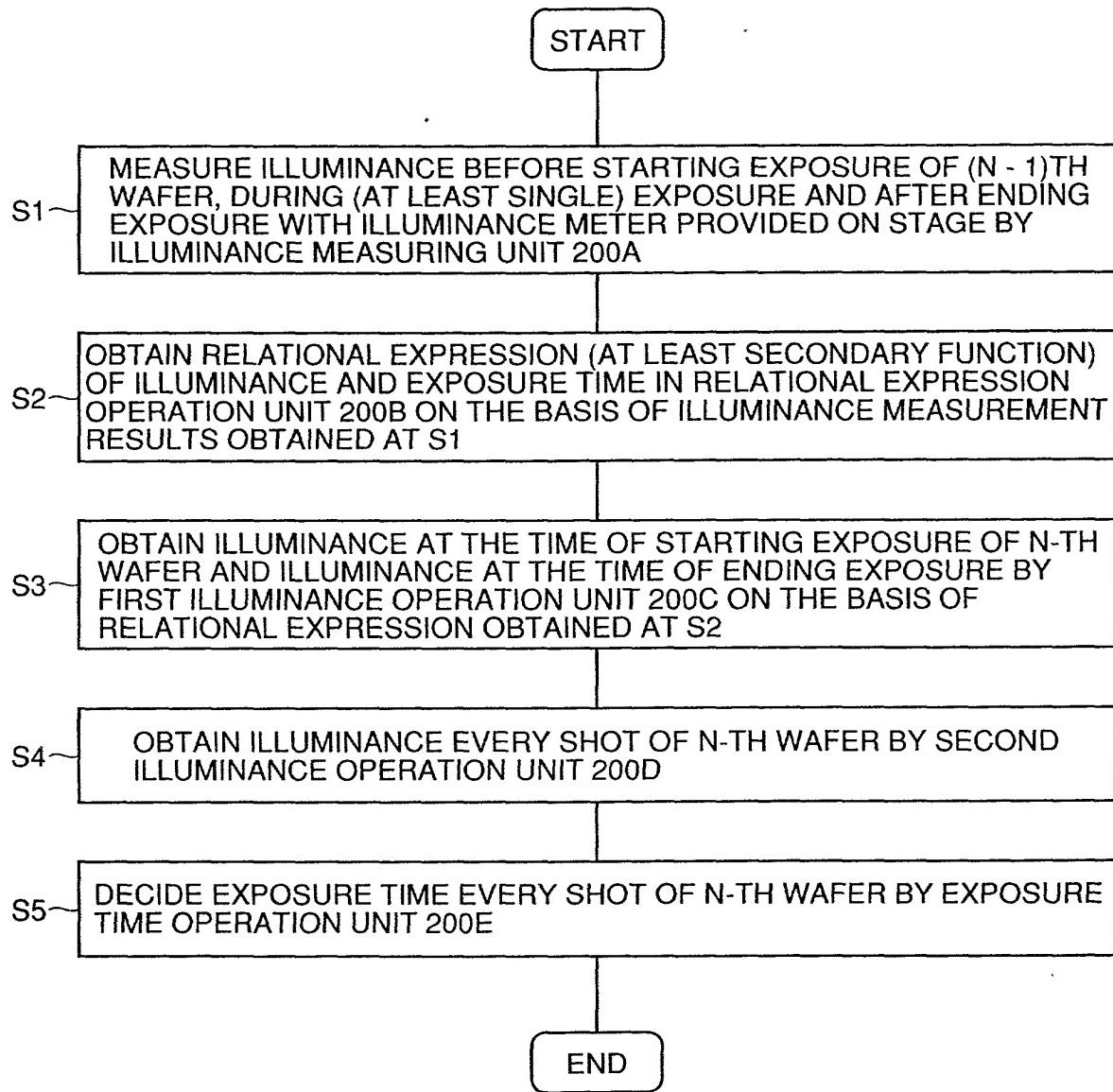
200E

EXPOSURE TIME OPERATION UNIT OBTAINING EXPOSURE  
TIME EVERY SHOT OF N-TH WAFER

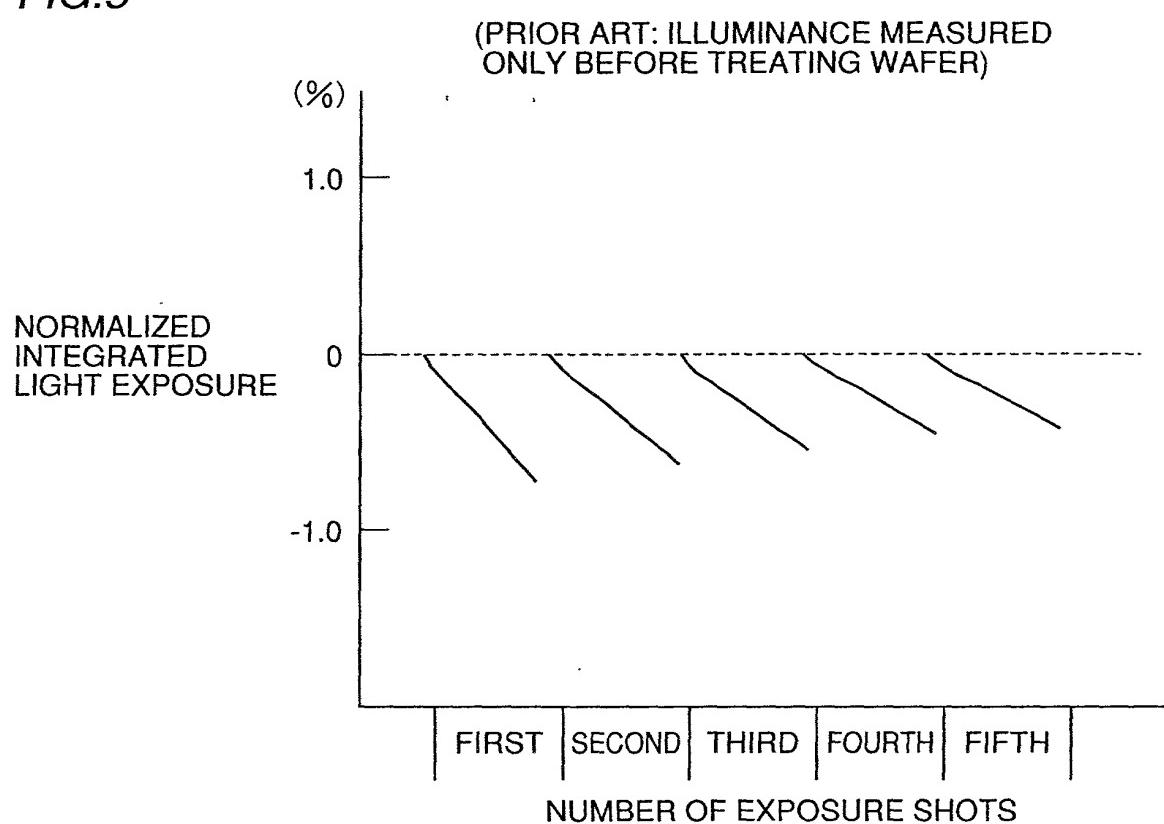
*FIG.3*



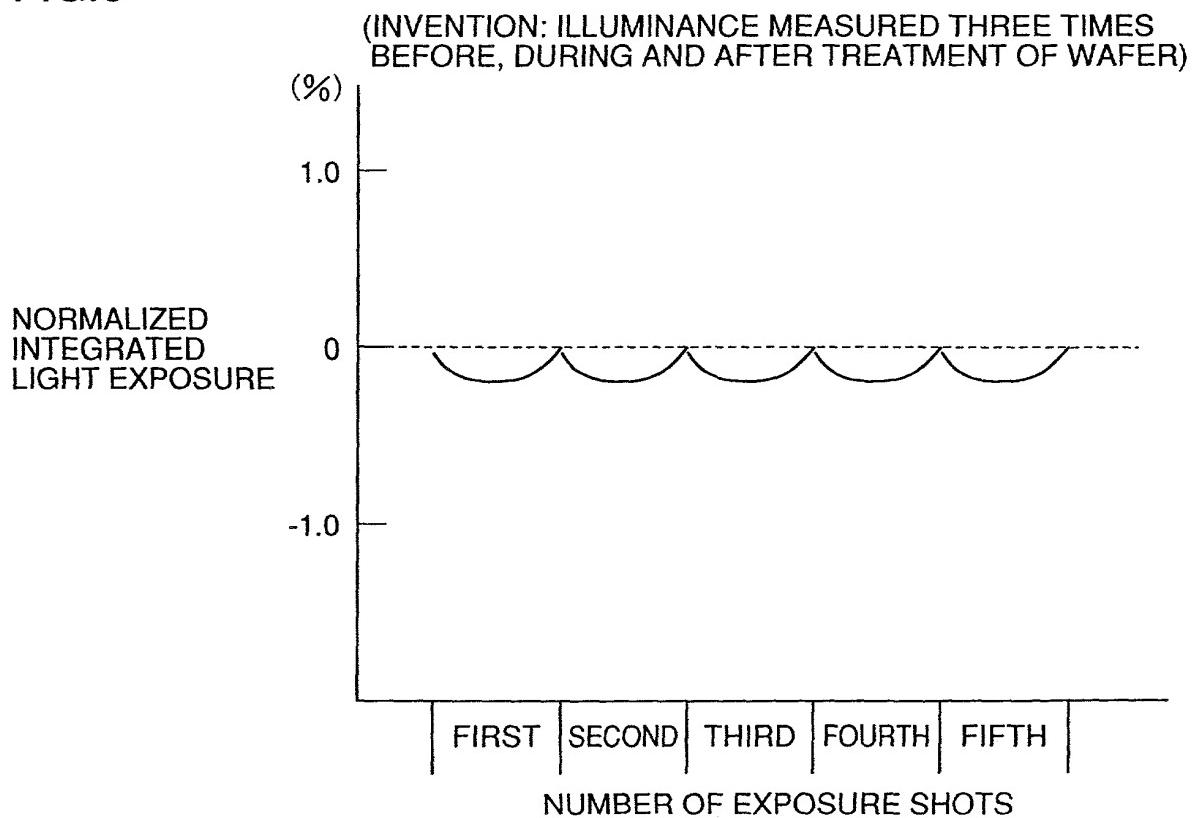
**FIG.4**



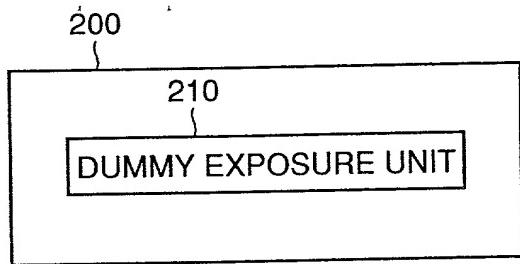
**FIG.5**



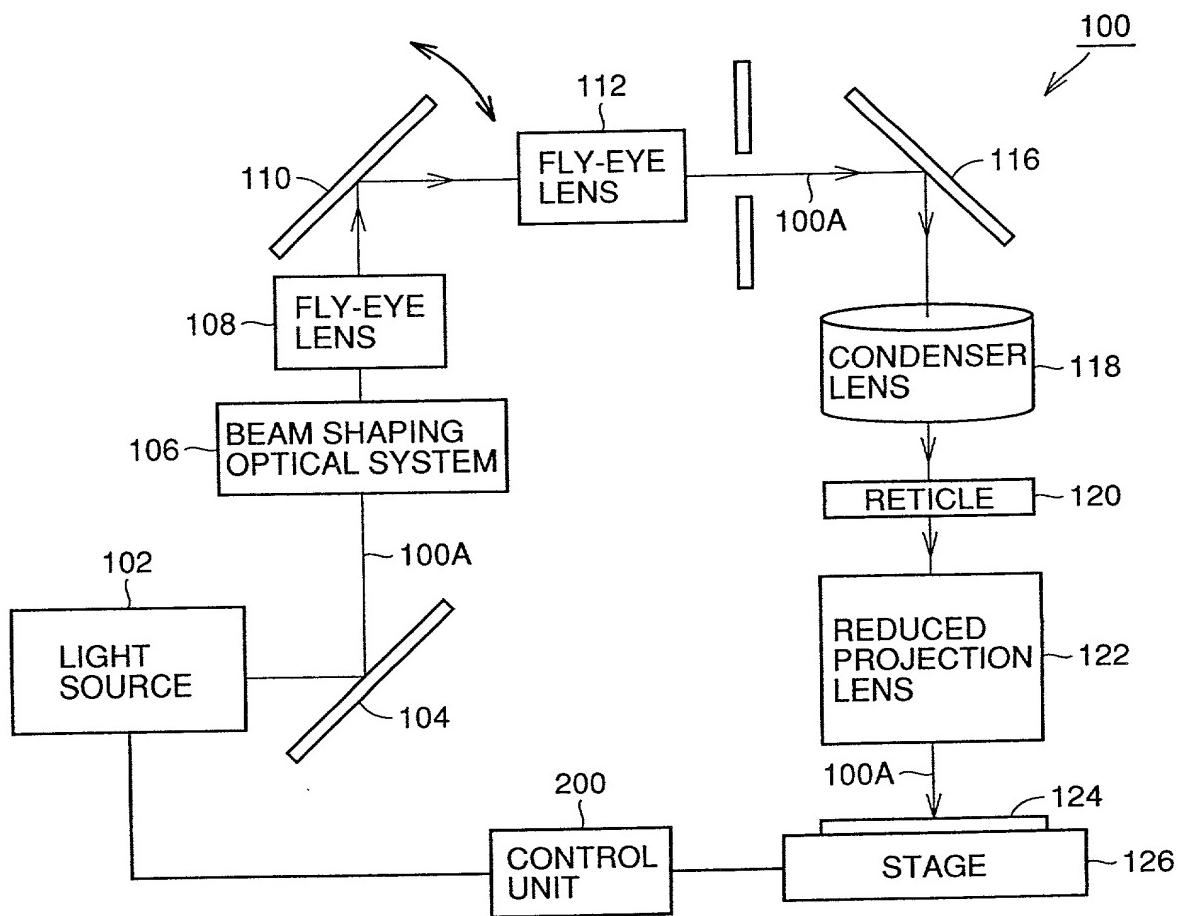
**FIG.6**



**FIG.7**



**FIG.8** PRIOR ART



*FIG.9* PRIOR ART

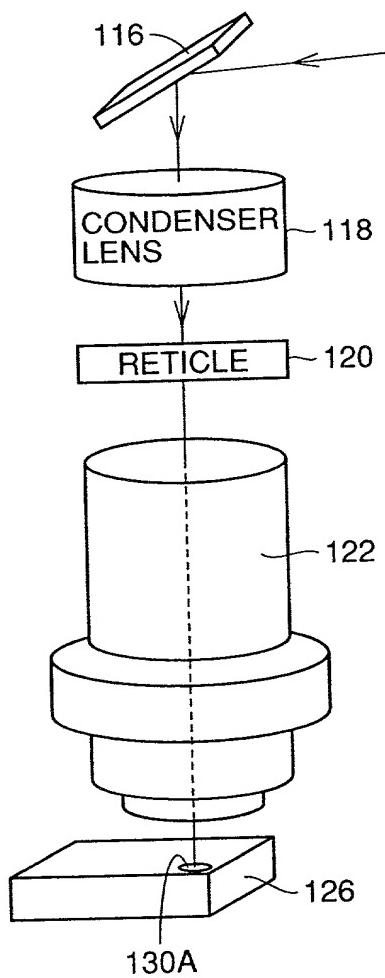


FIG. 10 PRIOR ART

